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a recipe selection method based on a trim amount

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Patents 1 - 10 on a recipe selection method based on a trim amount. (0.17 seconds)

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[APPLICATION] [Method of operating a system for chemical oxide removal](#)

US Pat. 10736983 - Filed Dec 17, 2003 - Tokyo Electron Limited

For example, a simple bin algorithm can be a control **recipe selection method** that is **based** on **trim** etch **amount**. If the selected control **recipe** settings are

...

[APPLICATION] [Formula-based run-to-run control](#)

US Pat. 10890410 - Filed Jul 14, 2004 - Tokyo Electron Limited, International Business Machines Corporation

For example, one process can comprise determining a **trim amount**, ... can use an algorithm (a Control **Recipe selection method**) **based** on **trim** etch **amount**. ...

[APPLICATION] [Method and system for realtime CD microloading control](#)

US Pat. 10464479 - Filed Jun 18, 2003

The **trim** and etch **recipe selection** is **based** on algorithms and/or equations ... such that the isolated and dense patterns are not **trimmed** by the same **amount**;

...

[Feature dimension deviation correction system, method and program product](#)

US Pat. 7289864 - Filed Jul 12, 2004 - International Business Machines Corporation, Tokyo Electron Limited

Currently IMs are typically optically (scatterometry) **based** tools. a process model converts a **trim amount** to a process **recipe** parameter set (for ...

[Method and system for line-dimension control of an etch process](#)

US Pat. 7291285 - Filed May 10, 2005 - International Business Machines Corporation

In step 265 an etch time for the mask **trim** etch process is calculated **based** on the ... over a range **based** upon said value of WT1; T_{jj}^n = said total **amount** of

...

[Method of using a wafer-thickness-dependant profile library](#)

US Pat. 7571074 - Filed Jan 30, 2007 - Tokyo Electron Limited

... 5 tune, and/or optimize a measurement **recipe** and/or library **selection**, ... value can be fed forward **based** on pre-etch measurements and etch **trim amount**.

...

[Iso/nested control for soft mask processing](#)

US Pat. 7328418 - Filed Feb 1, 2005 - Tokyo Electron Limited

Formula- **based** models can comprise equations that contain the piece- 65 wise associations of desired results with **recipe** variables **based** on some evaluated

...

[APPLICATION] [Method of Using a Wafer-Temperature-Dependant Profile Library](#)

US Pat. 11668654 - Filed Jan 30, 2007 - TOKYO ELECTRON LIMITED

When a newly tuned and/or optimized measurement **recipe**, profile, ... value can be fed forward **based** on pre-etch measurements and etch **trim amount**. ...

Wafer-to-wafer control using virtual modules

US Pat. 7212878 - Filed Aug 27, 2004 - Tokyo Electron Limited, International Business Machines Corporation


The desired process result may comprise a **trim amount**, an etch **amount**, ... The WM control strategy **selection** and initiation can be context-**based**. ...

Methodology for repeatable post etch CD in a production tool

US Pat. 6858361 - Filed Sep 9, 2002

The **method** of claim 3, an **amount** of photoresist **trimmed** varies nonlinearly ... comprising choosing an etch **recipe** for the etch process **based** on the measured ...

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